

OAI MASK ALIGNER MODEL 800



- Precise ($1\mu\text{m}$ - $2\mu\text{m}$) optical alignment accuracy
- Designed for semiconductor, MEMS front side and backside lithography and nanotechnology applications
- Precision level-to-level mask alignment
- Four-camera optical system for double sided alignment
- Interchangeable mask holders and chucks
- User-defined & controlled substrate-to-mask pressure
- Soft, hard and vacuum contact printing capability